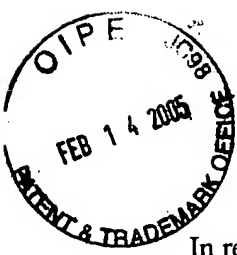


DFW



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q77760

OGATA, TOSHIYUKI, et al.

Appln. No.: 10/748,190

Group Art Unit: 1752

Confirmation No.: 5536

Examiner: Not yet assigned.

Filed: December 31, 2003

For: POSITIVE RESIST COMPOSITION AND BASE MATERIAL CARRYING LAYER OF
THE POSITIVE RESIST COMPOSITION

PRELIMINARY AMENDMENT

MAIL STOP AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Prior to examination, please amend the above-identified application as follows on the
accompanying pages.

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